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2	BRS	L2	31	1 same nano\$8	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/03/23 16:18
3	BRS	L3	49969	(lift-off or liftoff or (lift\$3 adj off))	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/03/23 16:19
4	BRS	L4	434	1 and 3	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/03/23 16:19
5	BRS	L5	890613	residu\$6	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/03/23 16:19

	Type	L #	Hits	Search Text	DBs	Time Stamp
6	BRS	L6	147	4 and 5	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2004/03/23 16:37

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multi—

PREFIX: **1.** Many; much; multiple: *multicolored*. **2a.** More than one: *multiparous*. **b.** More than two: *multilateral*.

ETYMOLOGY: Middle English, from Old French, from Latin, from *multus*, much, many. See *mel-*² in Appendix I.

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